



IEEE SW Test Workshop

Semiconductor Wafer Test Workshop

June 8 - 11, 2014 | San Diego, California

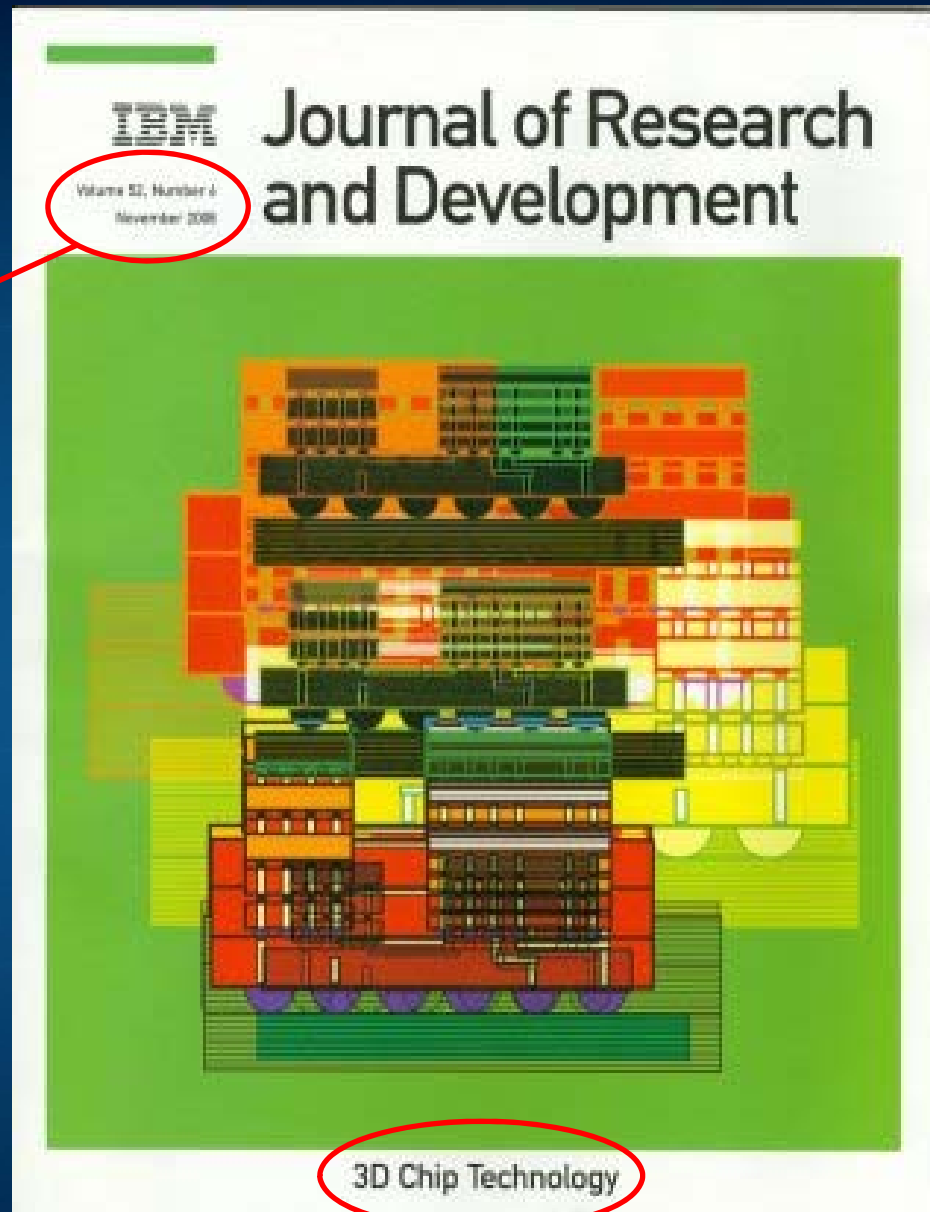
Transferable Fine-Pitch Probes



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IBM T.J. Watson Research Center

Overview

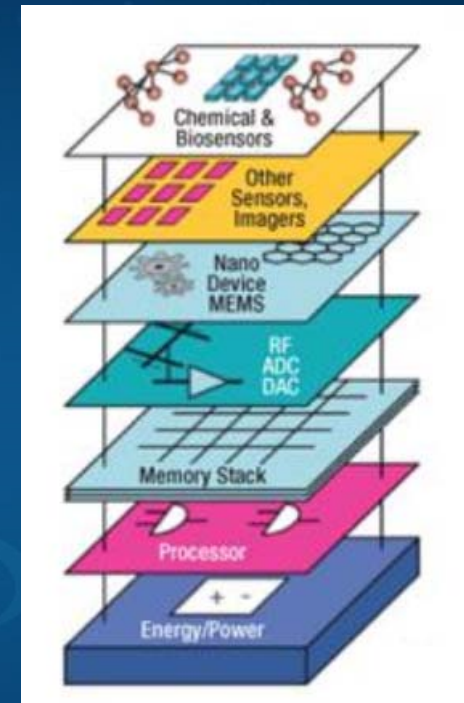
- **Motivation (3D Si, “smart” probe)**
- **Transferrable probe tip process**
- **Issues**
- **Test vehicles, apparatus**
- **Contact resistance, force, max current**
- **Touchdown quality to date**
- **Probe stations in the future**



2008

3D Integration

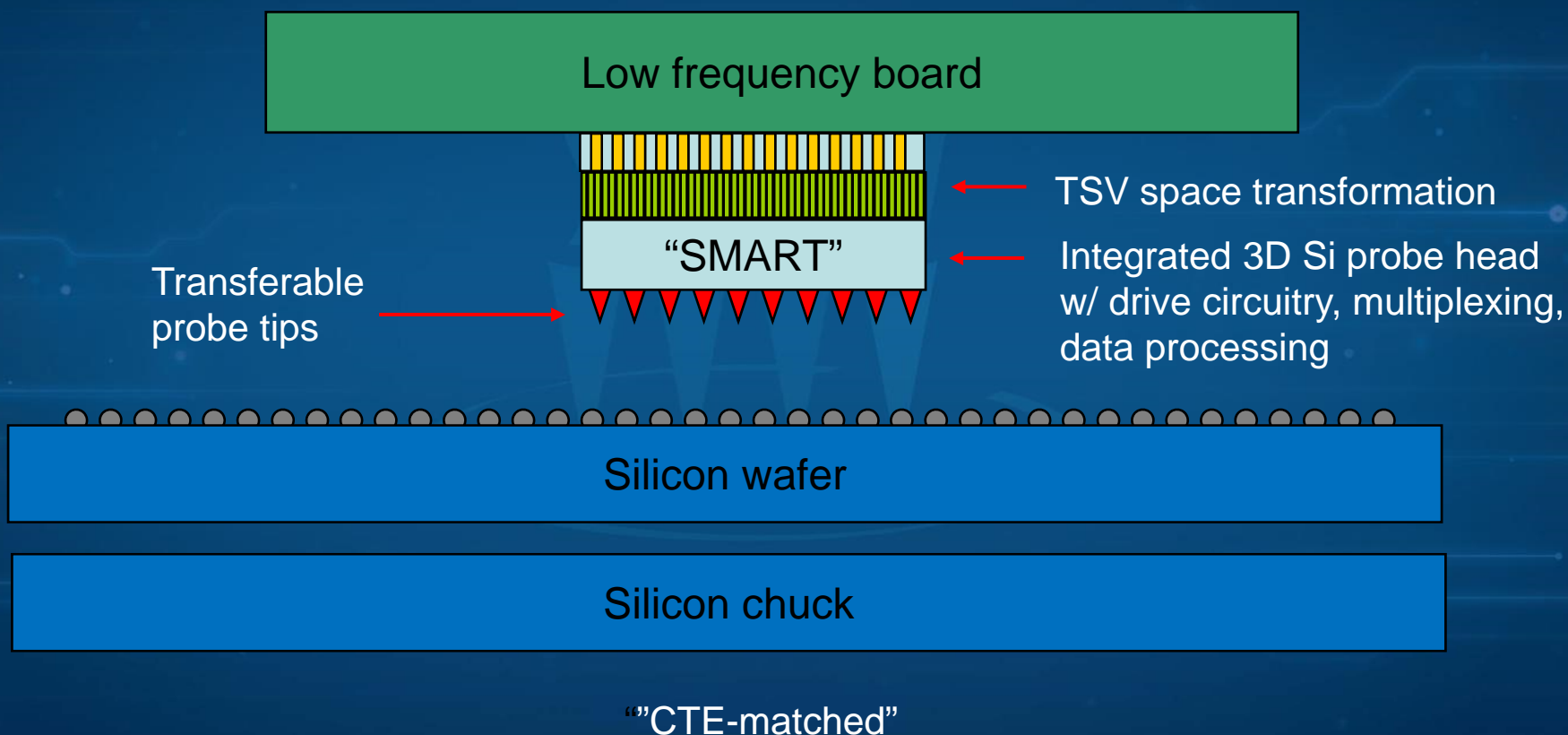
Benefits	Challenges
Reduced package thickness and area	Bond and assembly
Reduced package complexity	Cooling
Improved performance (fine pitch & short length interconnections)	Design methodology
Mixed chip technologies	Test for KGD, KGS
Reduced cost (holistic view)	Increased cost (Si processing viewpoint)



Future-fab.com

Fine Pitch / 3D Probing

“Poll” the SMART probe for analyzed test results



Example: L. Namburi,
G. Maier SWTW 2013

Transferable Tips



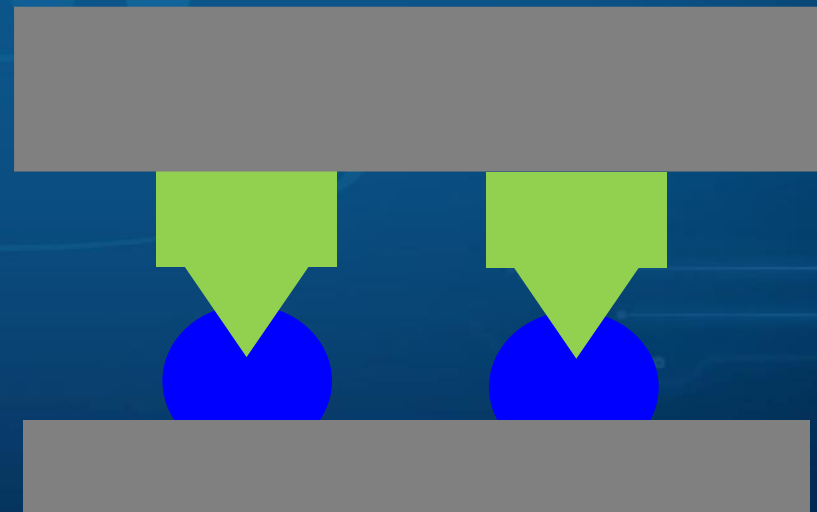
silicon mold (anisotropic etch)



Fill with metal and build metal pillar

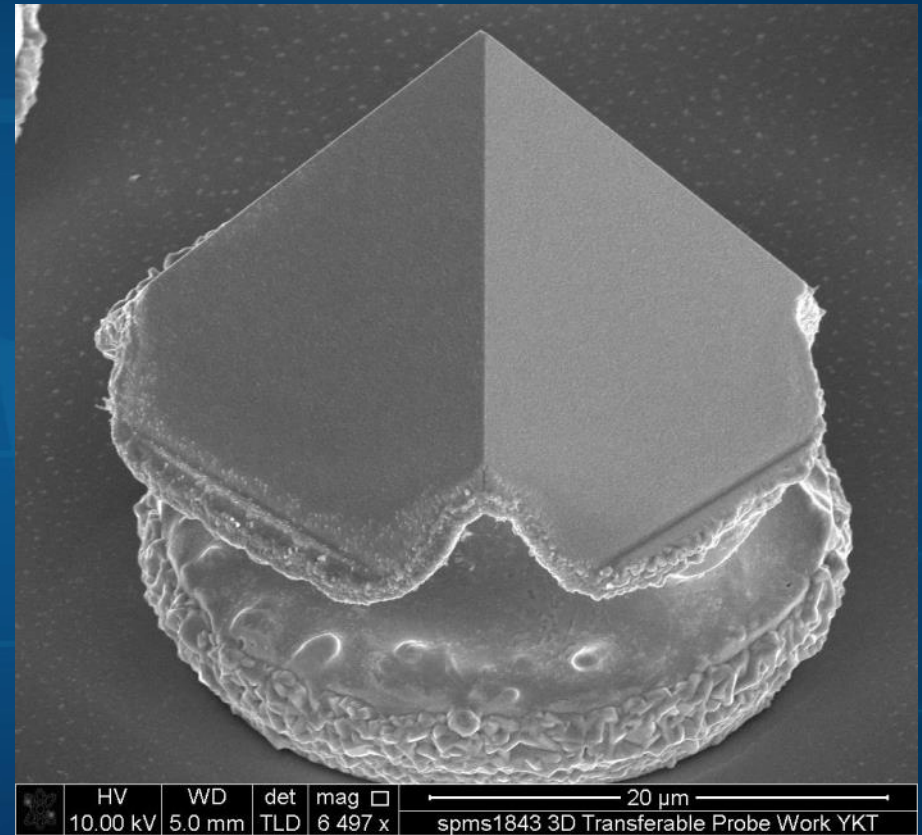
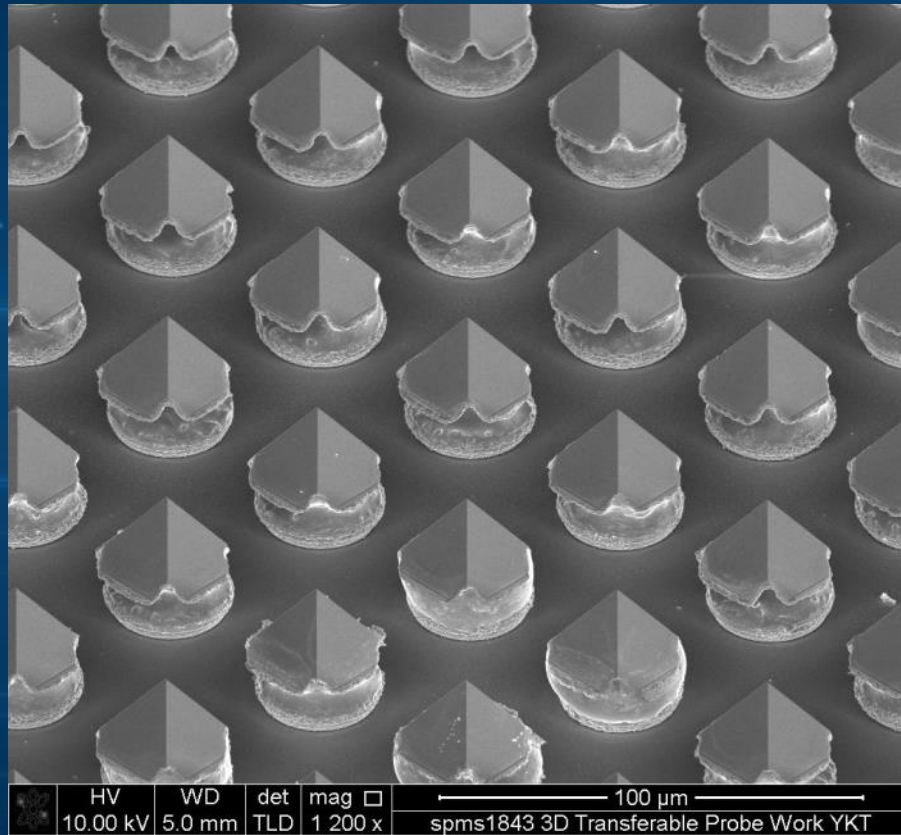


Release



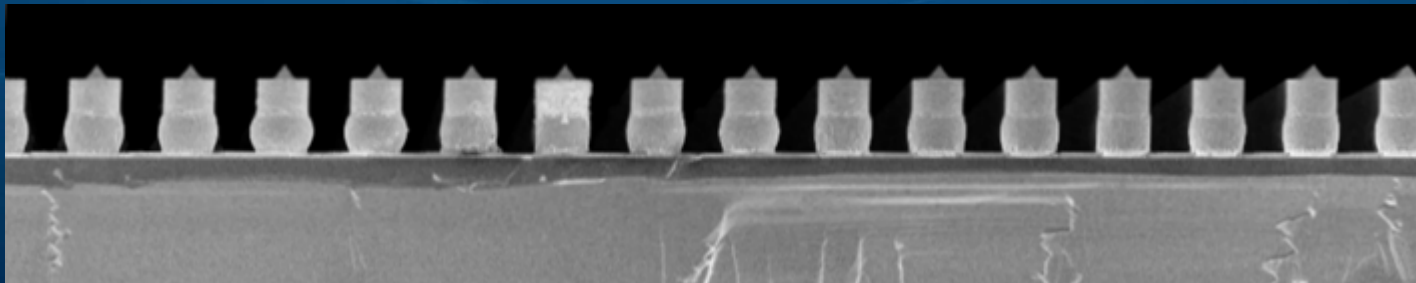
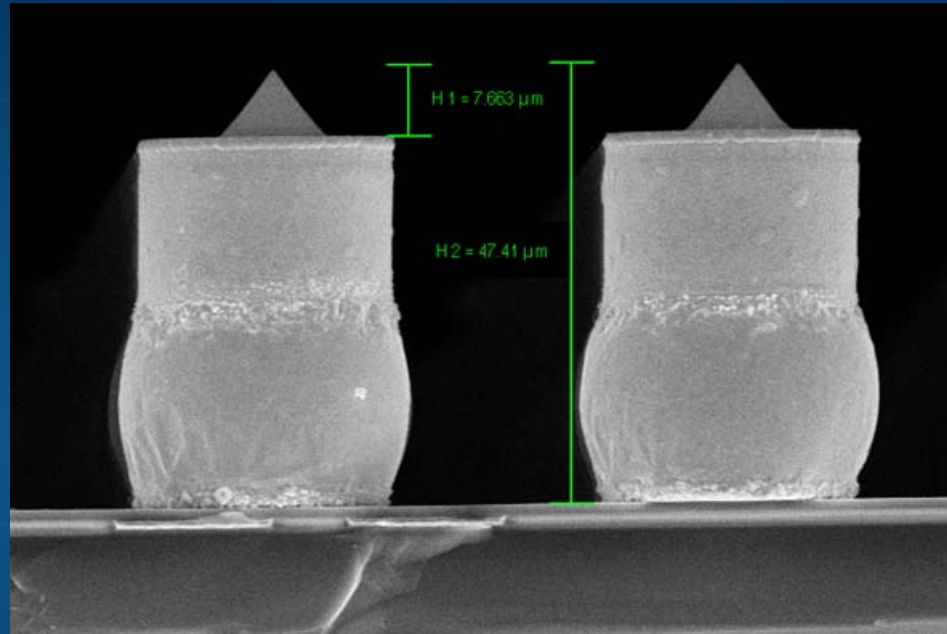
Test

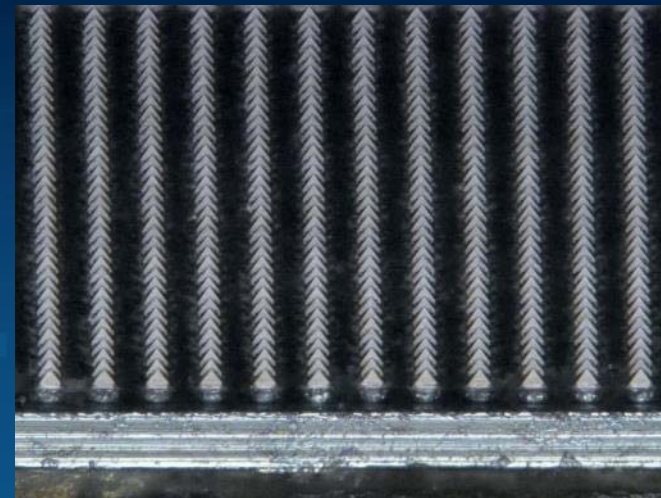
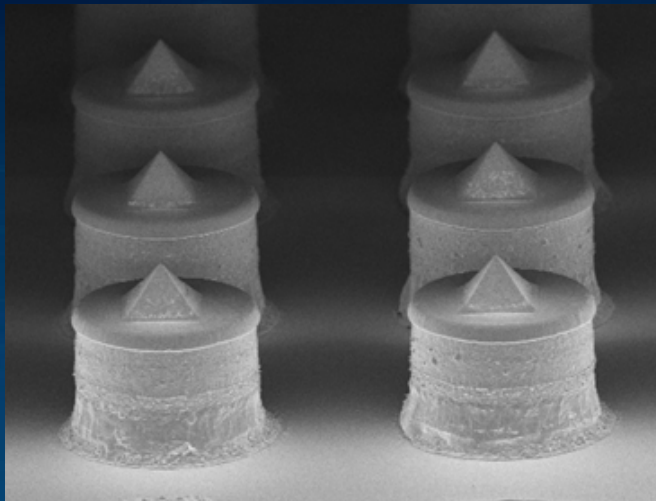
1st Generation



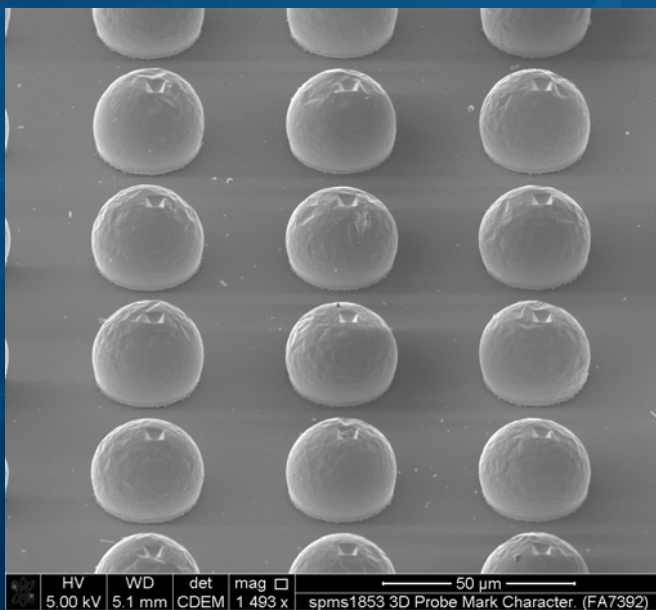
Tips are 4-sided pyramids with 70.5 degree cone angle.

2nd Generation

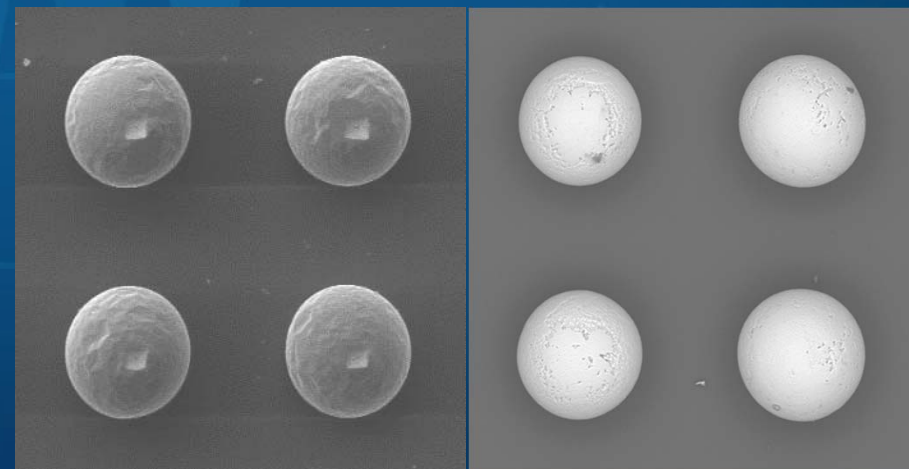




Transferable probe tips on 50 μm 3D silicon chip



Uniform probe marks



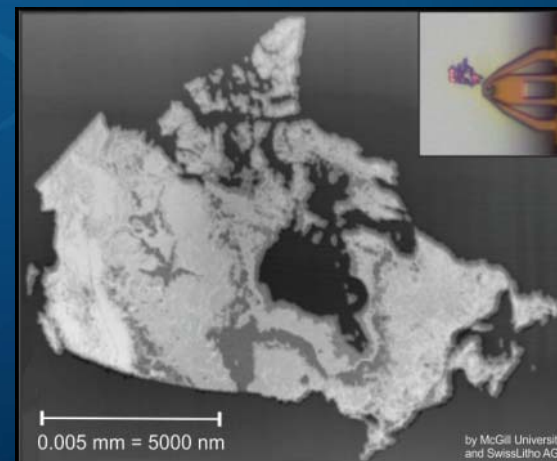
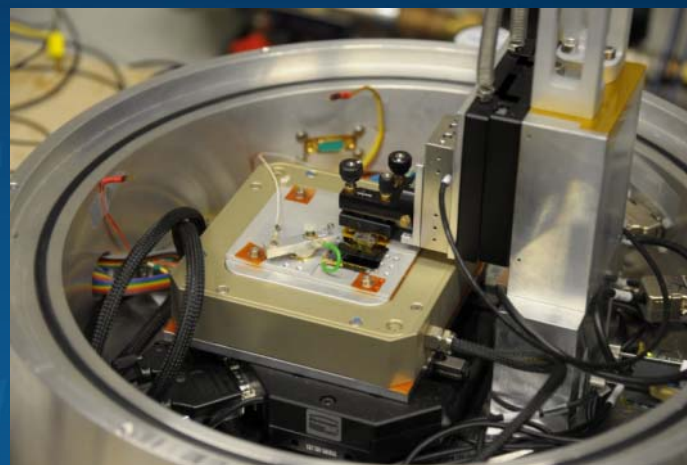
Solder recovery at 250° C in formic acid atmosphere.

Transferable Tips

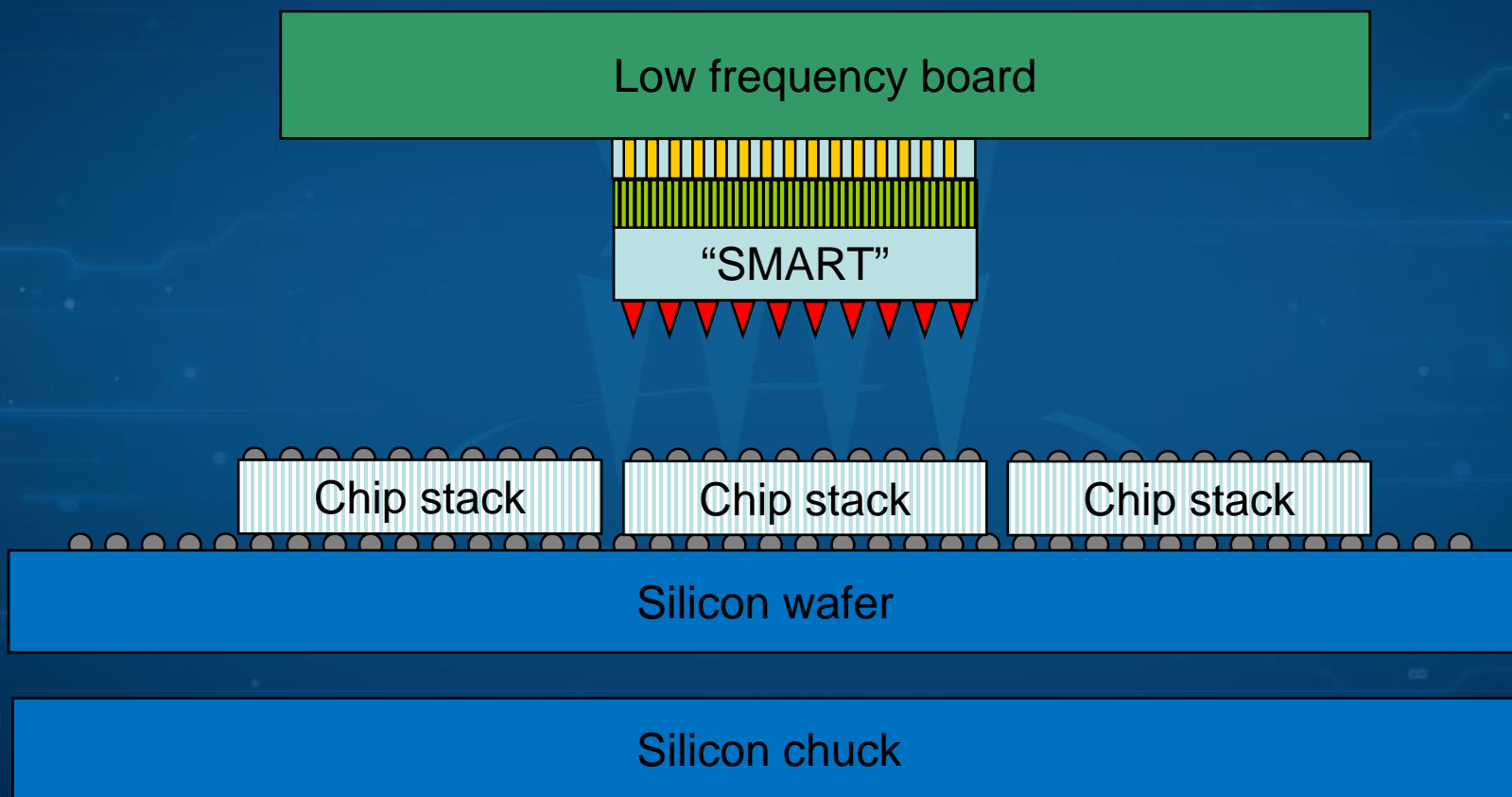
- **Low-temp process**
- **Variety of possible tip materials**
- **Variety of possible substrates**
 - Silicon, ceramic, glass, laminate, MEMs structure
- **Precise size, shape, location**
- **Precisely planar**
- **Non-compliant versions to-date**
 - Large compliance requires MEMs structure

IBM Zurich Nanotip (2014)

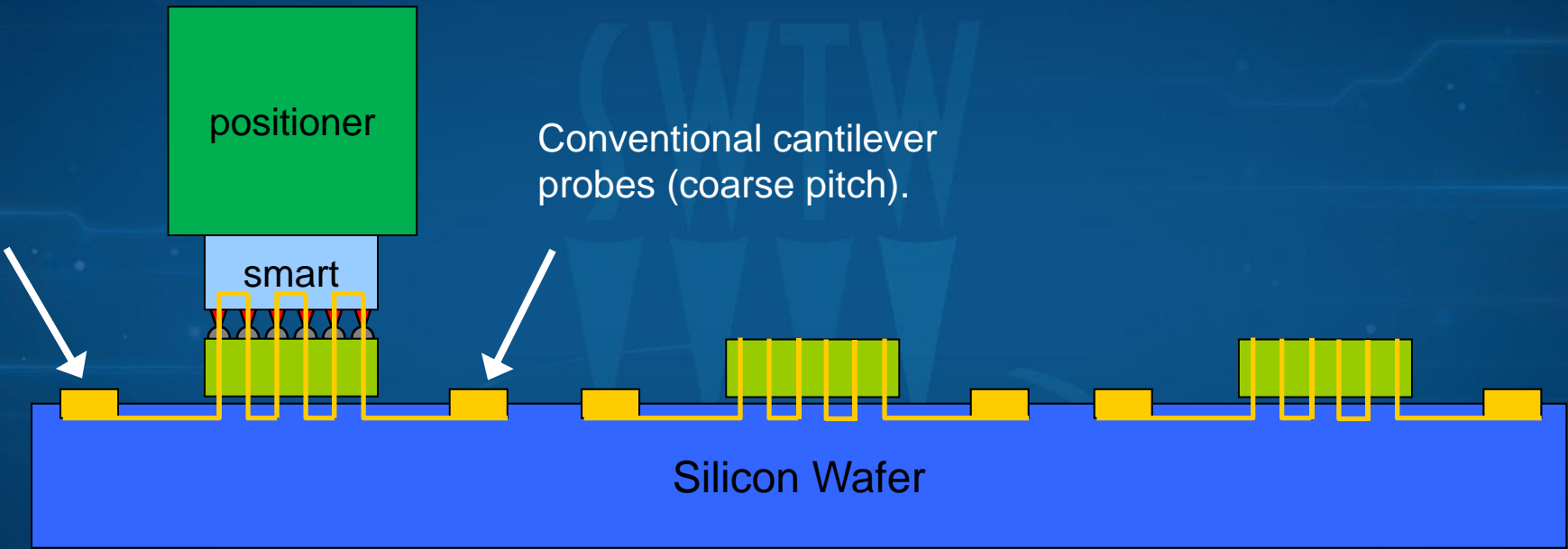
- “nm-sized” tip, 1000 °C
- “chisel” into polymer
- 10 nm resolution
- $\leq 40\text{nm}$ penetration
- 11x14 μm Panda image in 11 minutes
- 30 μm wide Canada image, 1 Mpix in 1 min? (McGill Univ)
- Licensed to SwissLitho
 - “NanoFrazor”



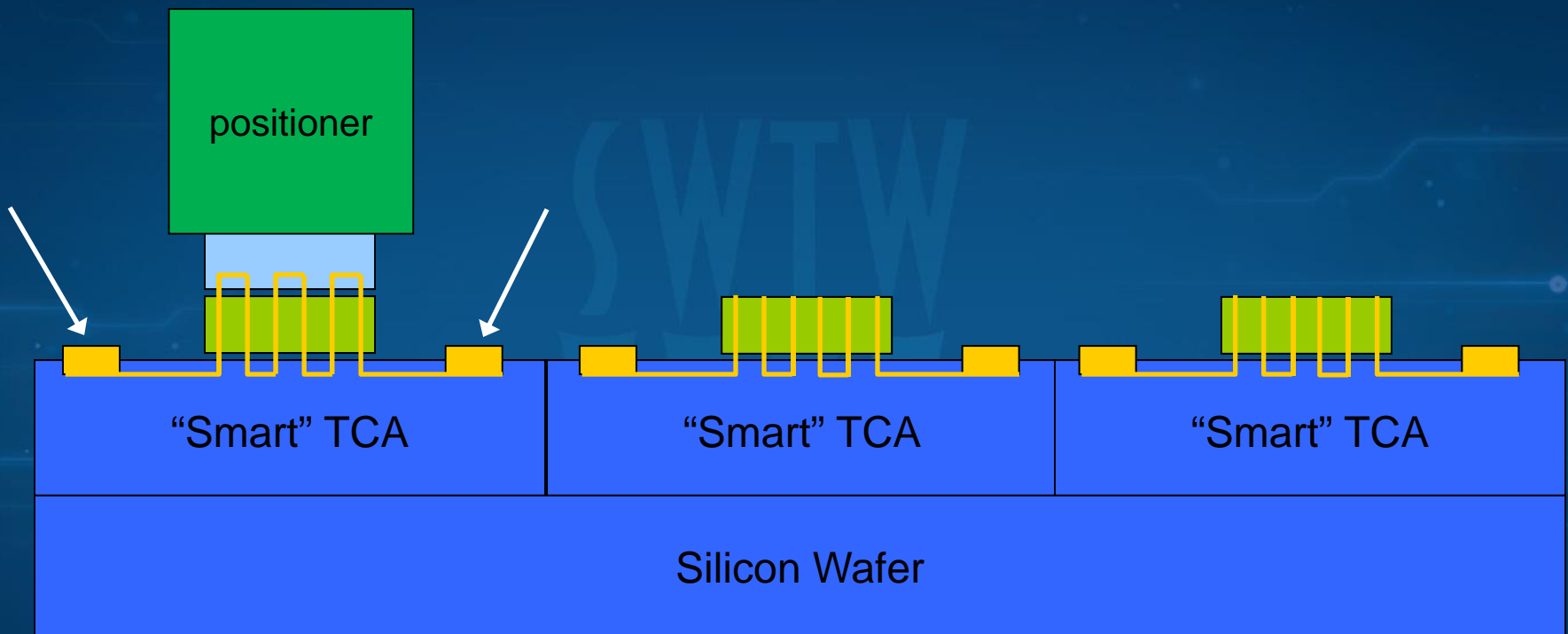
Fine Pitch / 3D Probing



Hybrid Probe Mode



Hybrid Probe Mode w/“Smart” Temporary Chip Attach (TCA) Wafer



Issues

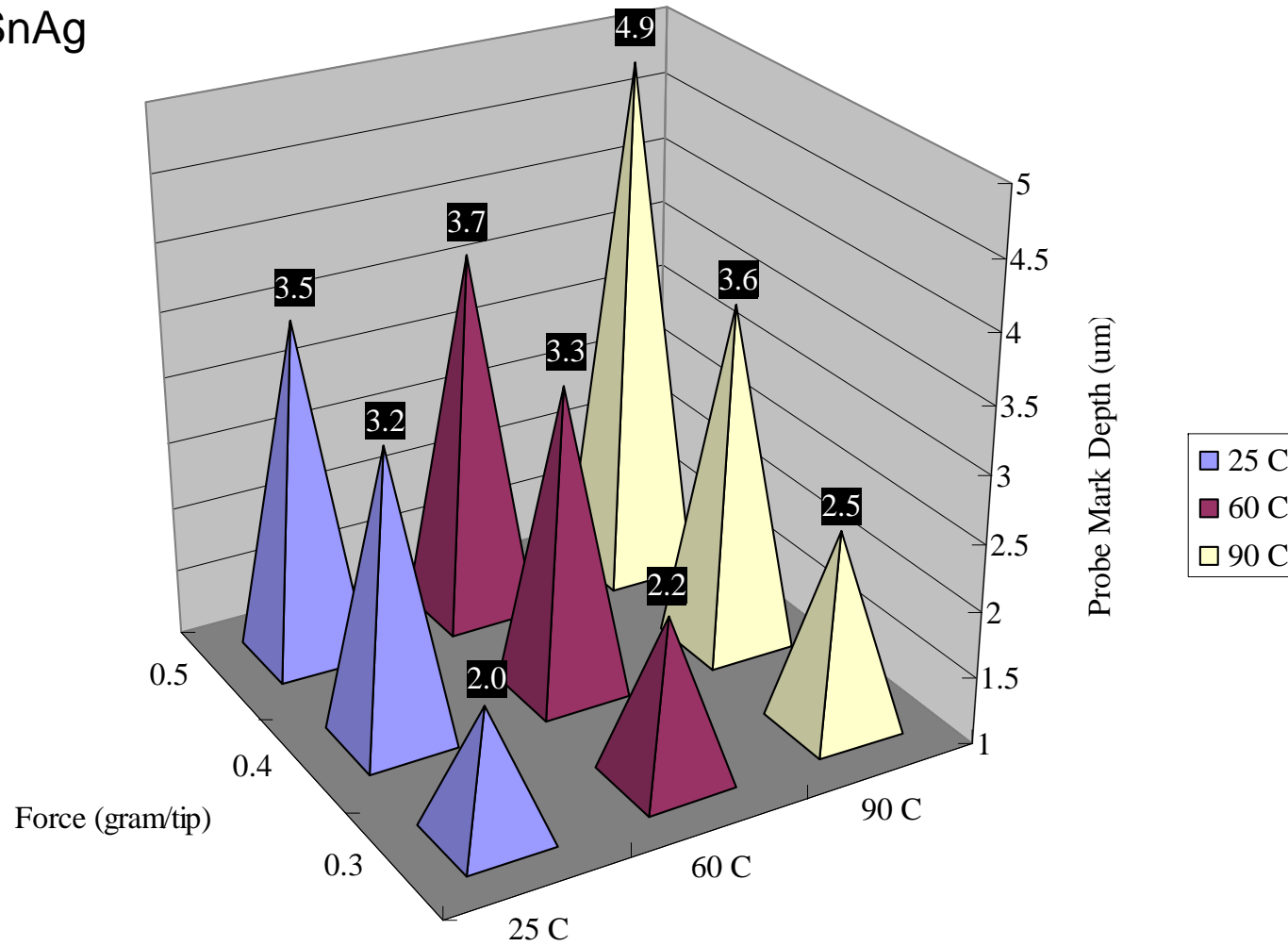
- **Convert processor chip into probe head**
 - Low-temp tip transfer process on thin die
- **Need 3D Si technology for space transformer**
- **Tip integrity and contact**
 - Vertical indent (no scrub) with small force
 - Thermal expansion issues with high-power test?
 - Compliance needed?
- **Damaged probe head?**
 - Throw it away!

Compliance / Planarity

- **High interconnection yield with flip-chip bond**
 - Routine lab yield 99.999 to 99.9999 % (50 μm pitch)
 - Pads/melted bumps \rightarrow tips/bumps
- **Probe compliance issues**
 - Bump plating non-uniformity scales with thickness
 - 10% of 100 μm bump (200 μm pitch) is 10 μm
 - 10% of 15 μm bump (50 μm pitch) is 1.5 μm
 - Probe non-uniformity
 - Large over-drive required for many probe technologies
 - Not an issue with transferable tips.
 - Particle contamination
- **Do we need compliance?**

Flipchip "Tackdown" SnAg

Probe Mark Characterization



Probe Mark Depth vs Force and Temperature

PA300 (Suss/Cascade)

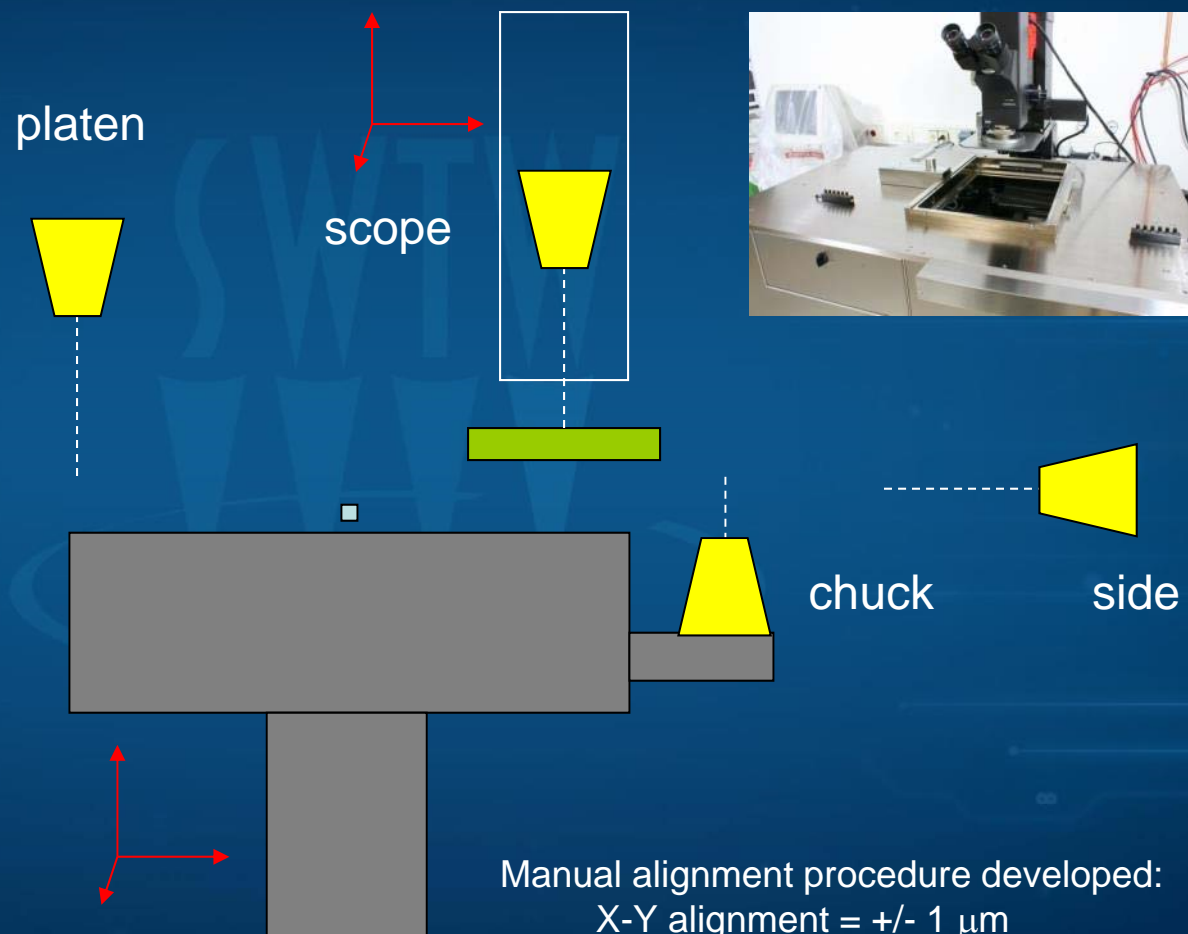
Chuck camera:
Probe theta correction
Probe mark position
Parallelism

Platen camera:
Chuck theta
Die mark position
"blob" position

Side camera:
Height adjustment
"near contact" view
Rough parallelism

Scope camera:
Initial setup
Parallelism
Post-test inspection

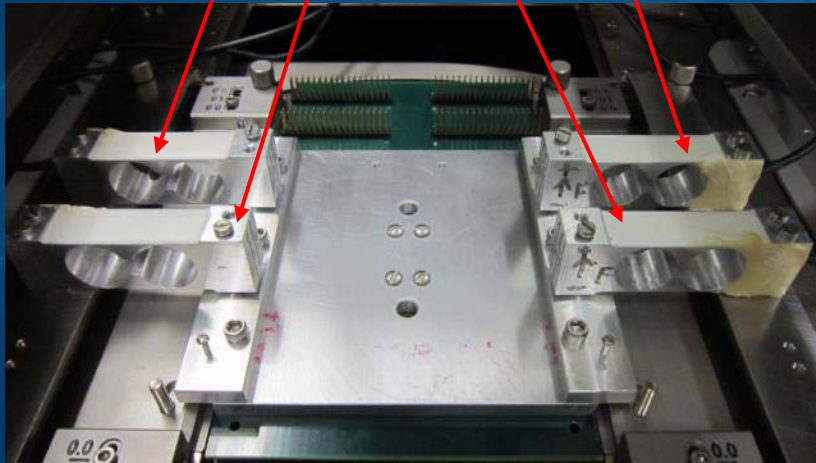
Note: none of the axes are perfectly aligned.



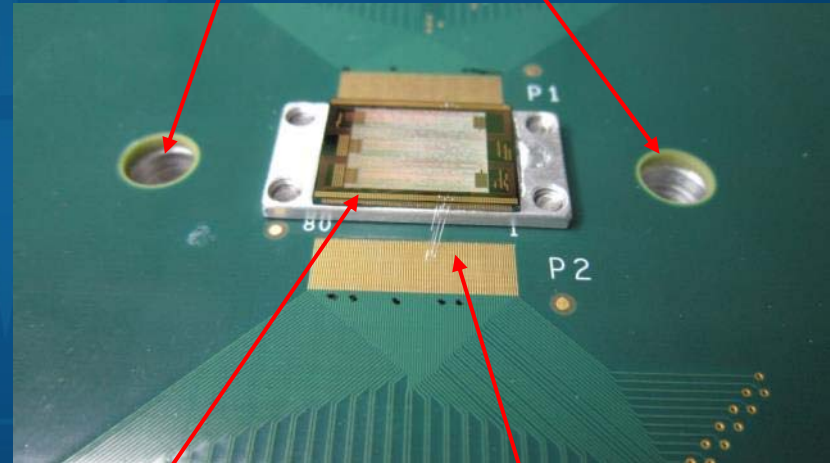
Manual alignment procedure developed:
X-Y alignment = +/- 1 μm
Z-parallelism ~ 2 μm at 10 mm (0.01 deg)

Probe Card

Force sensors



Observation holes



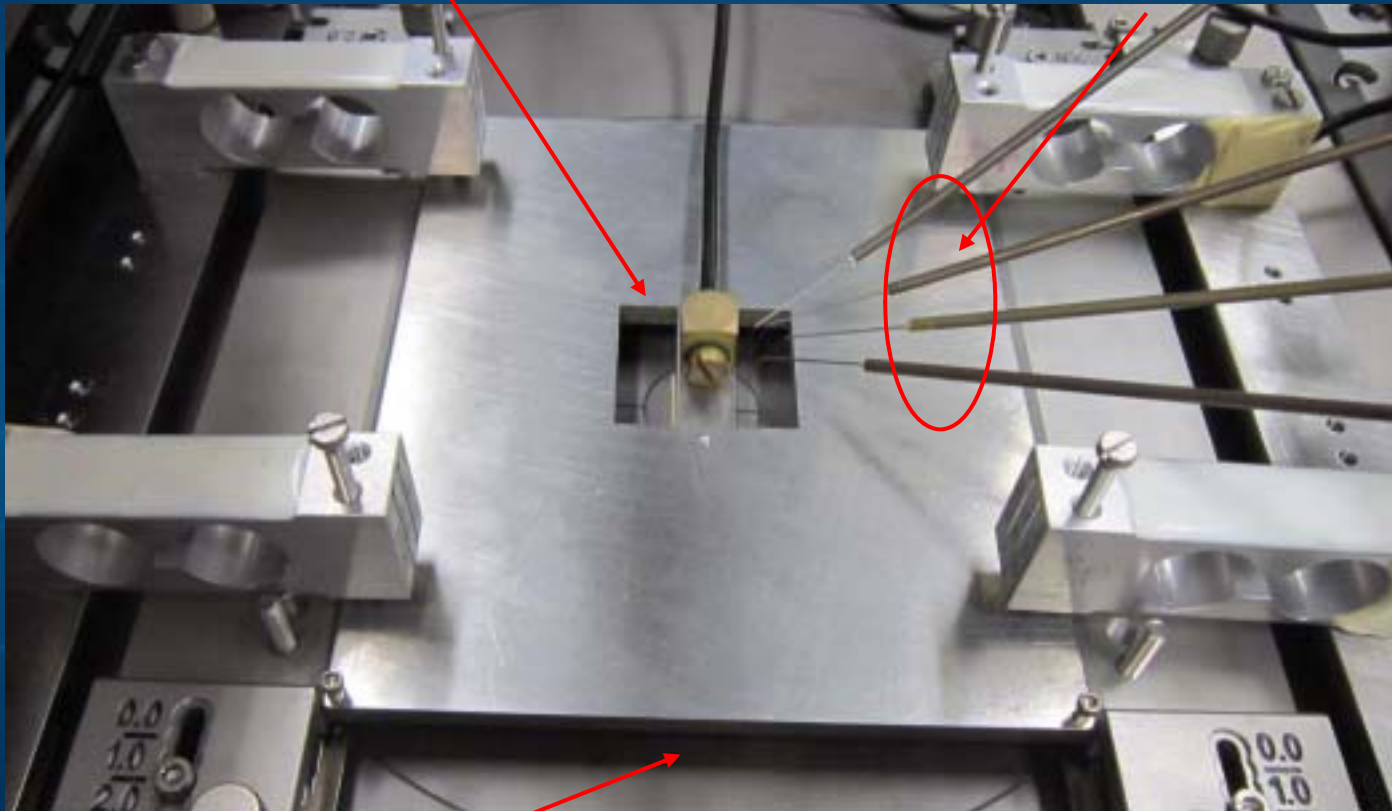
Probe die with tips

wirebonds

Hybrid Mode

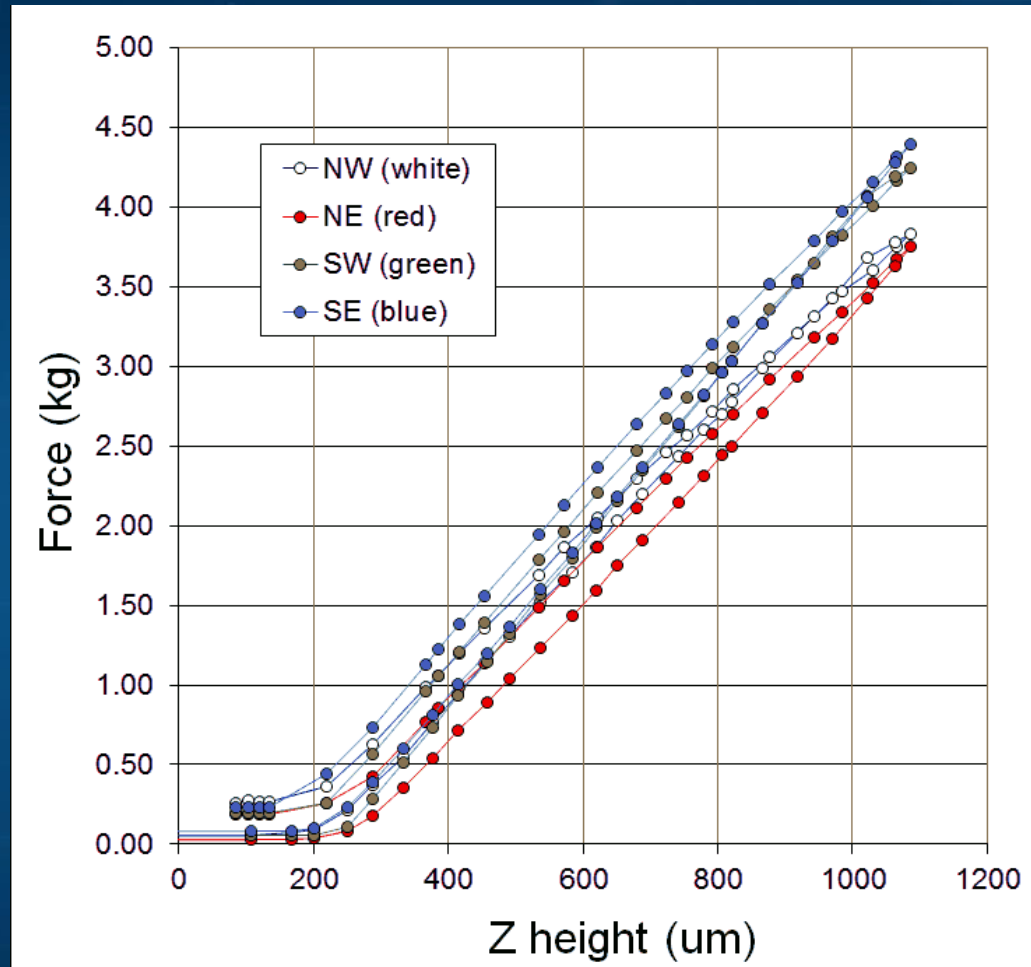
Top vacuum chuck w/bumped die

Manual probes



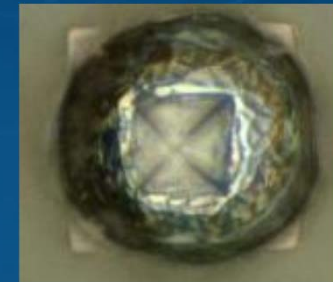
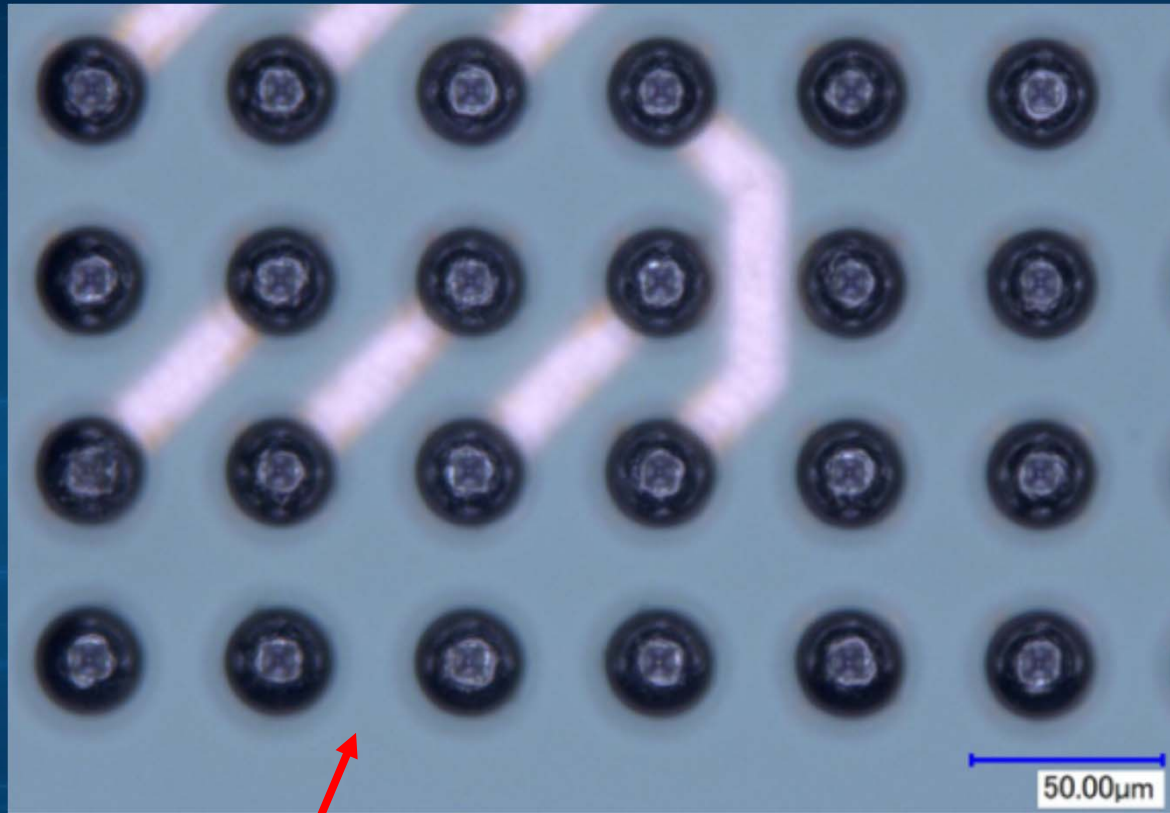
Bottom chuck w/probe tip die

Force Plot



Touchdown has "stabilized" when all four forces increase at the same rate.

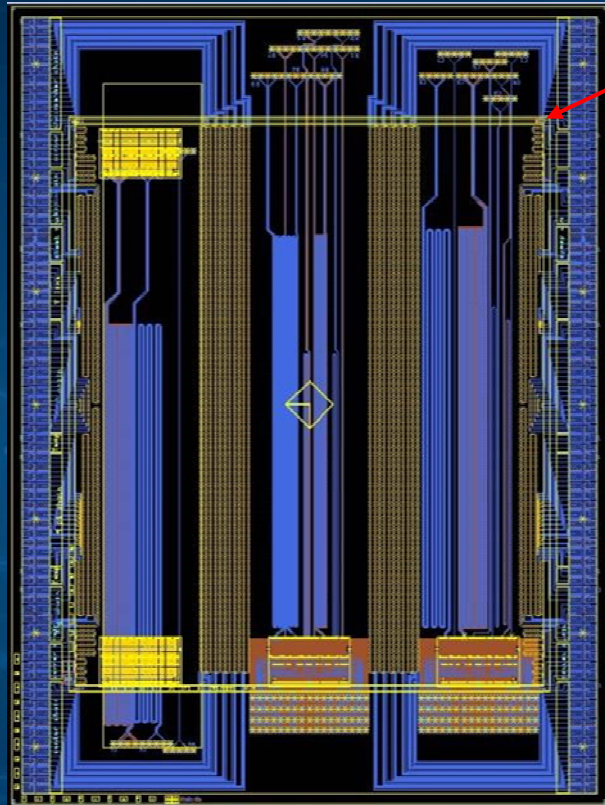
Probe Marks



“max” indent

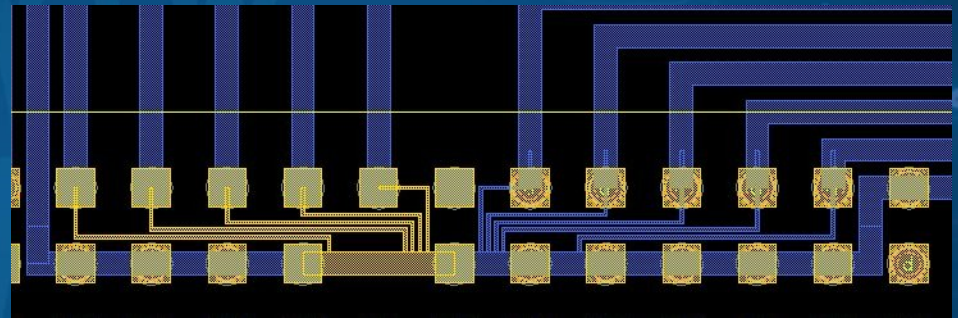
8x8 μm pyramid indent = 5.6 μm indent tip depth

Test Vehicle



Top die (bumped)

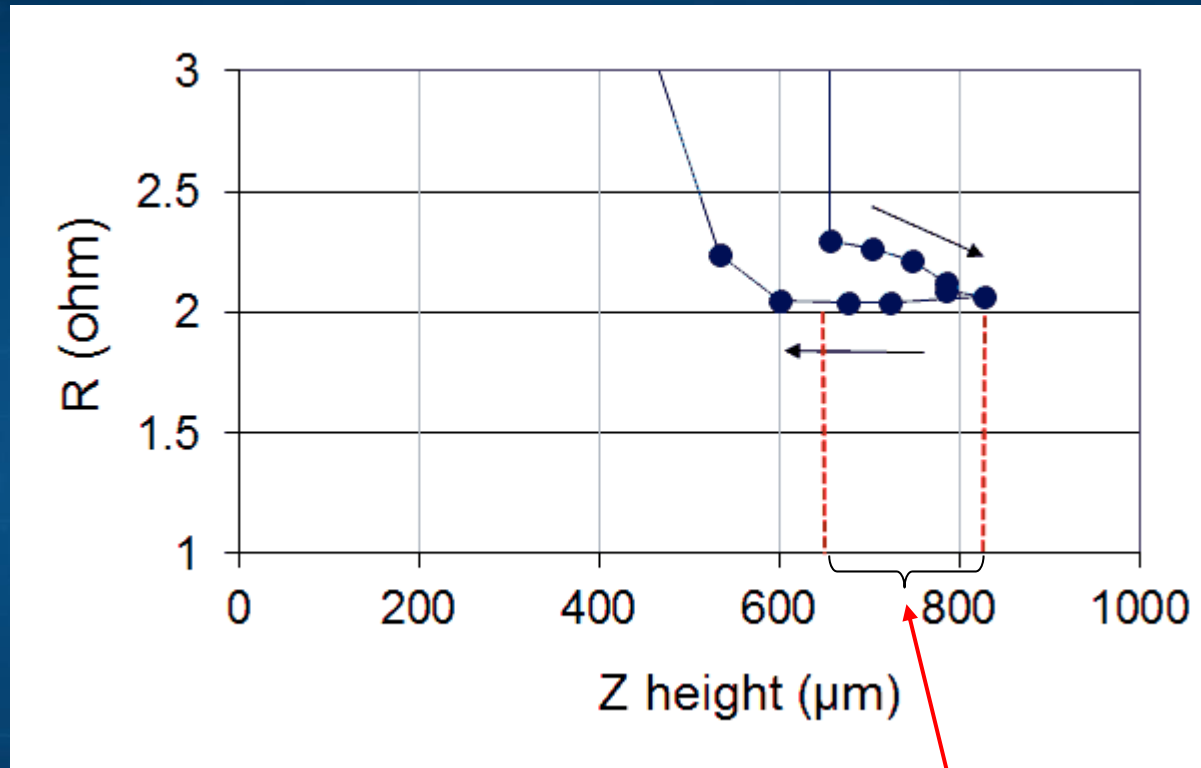
Bottom die (tip transfer)



Contact resistance sites (4-pt)

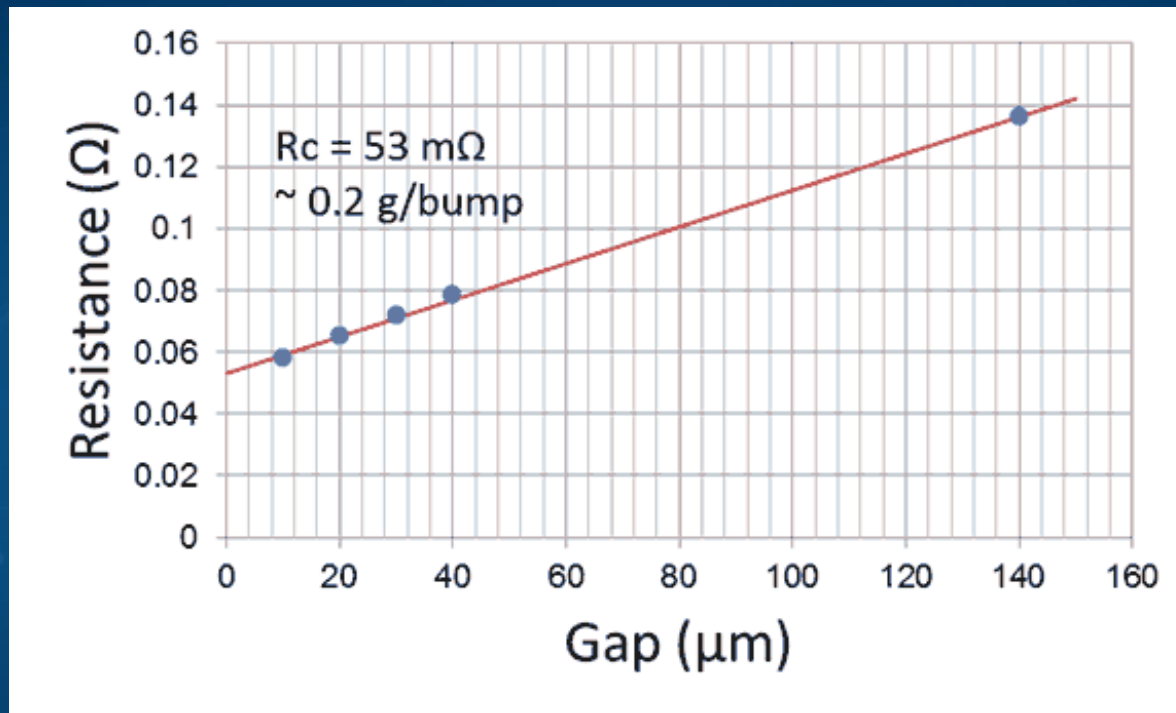
50 μm pitch
45,406 bumps (total)
12,644 electrically-testable bumps
Chain lengths from 1 to 230 links

3-pt Contact Resistance



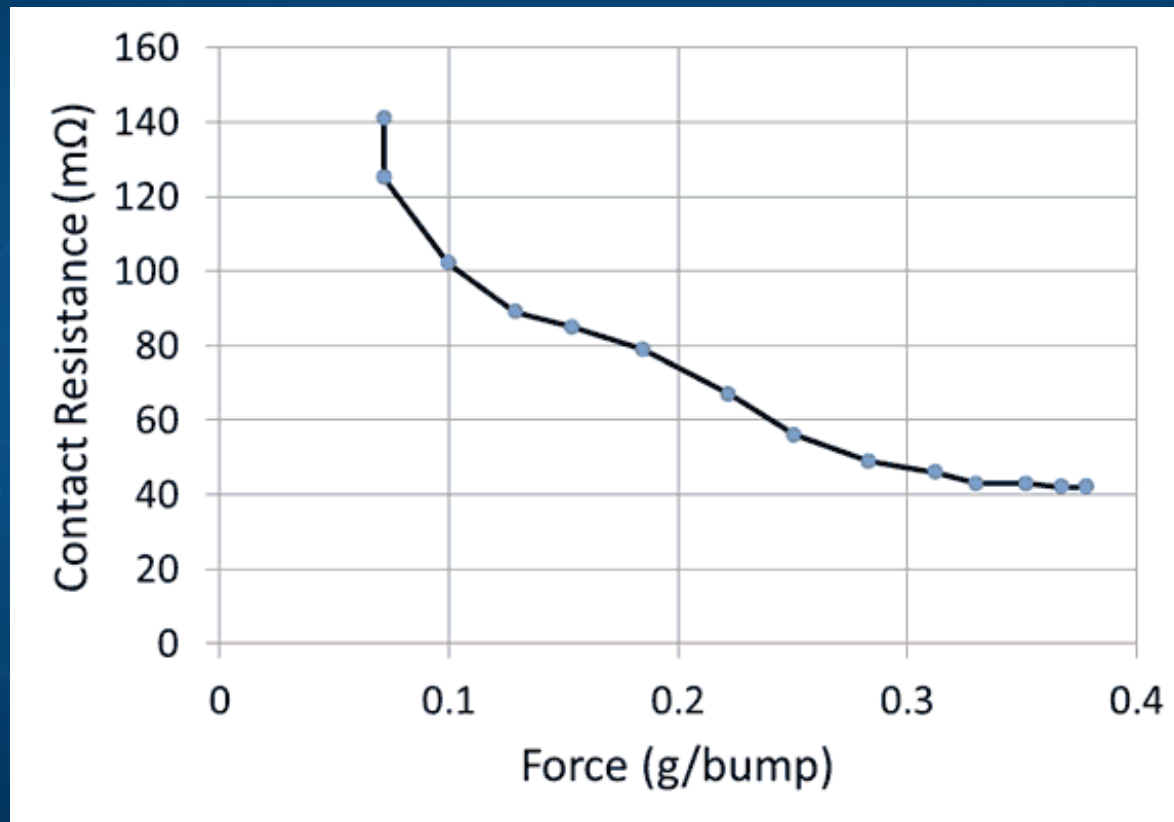
Additional force of ~ 0.01 gm/bump
reduced contact resistance by ~ 40 m Ω .

4-pt Contact Resistance

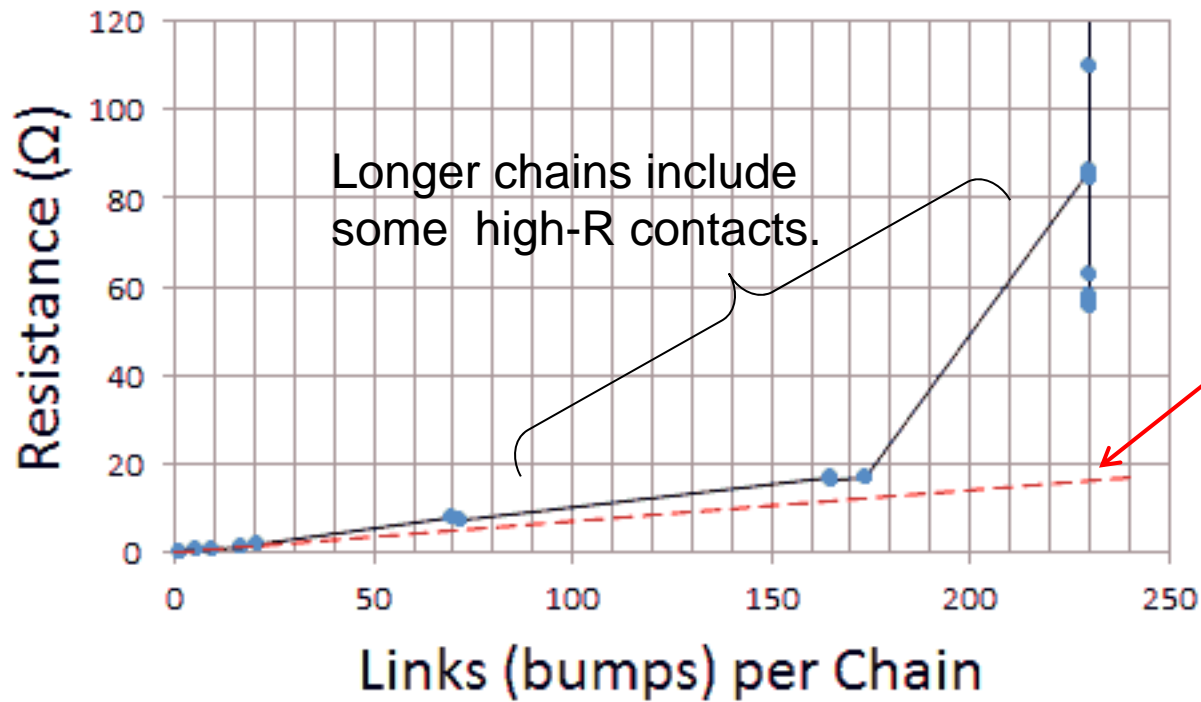


R_c depends upon probe force, "good" contact at 0.05 - 0.5 g/bump.
Lowest R_c measured thus far $\sim 30 \text{ m}\Omega$
Typical $R_c = 10\text{-}30 \text{ m}\Omega$ in joined parts (melted bump/pad)

Contact Resistance and Force



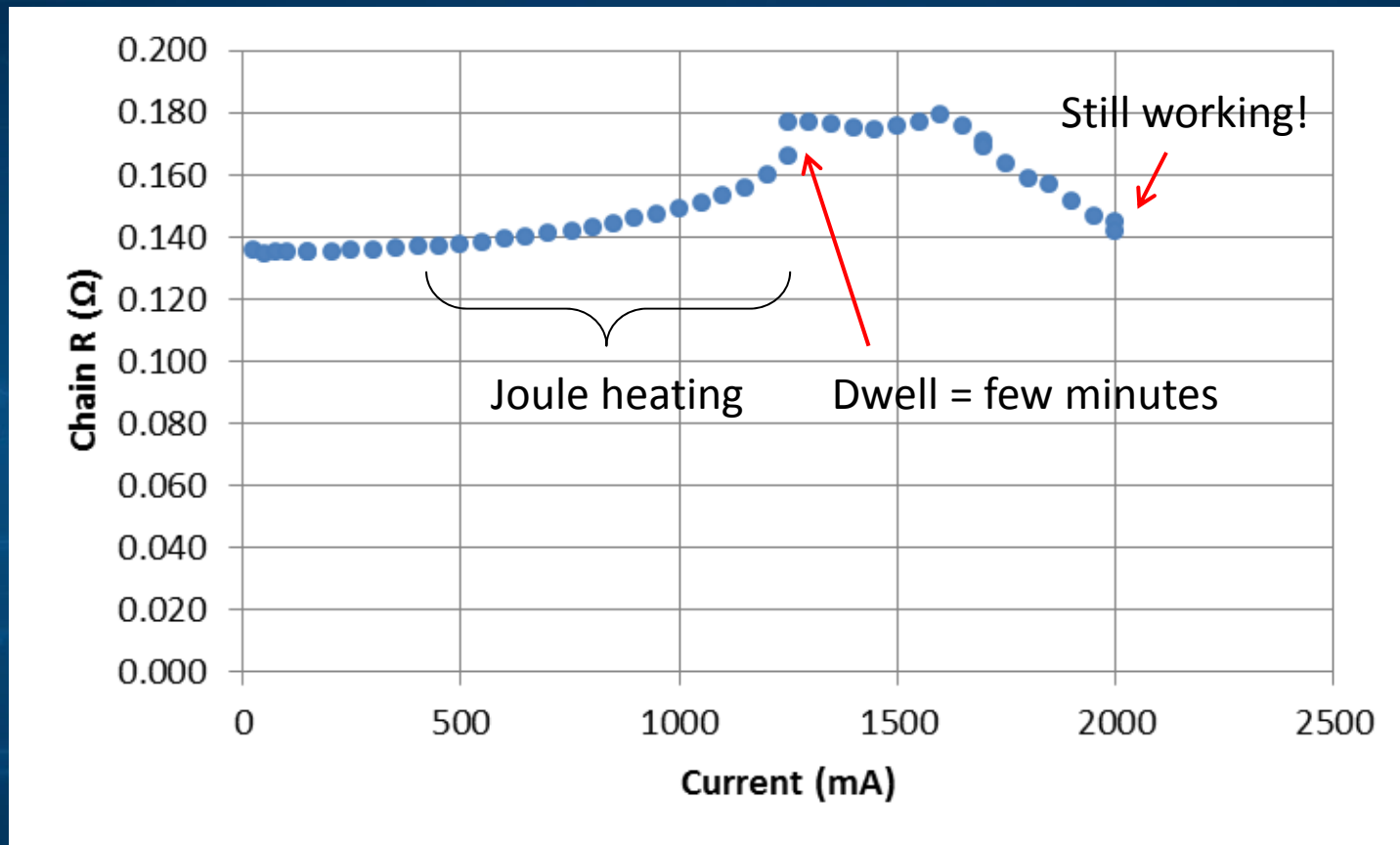
Chain Resistance



Linear fit to data up to 21 links.

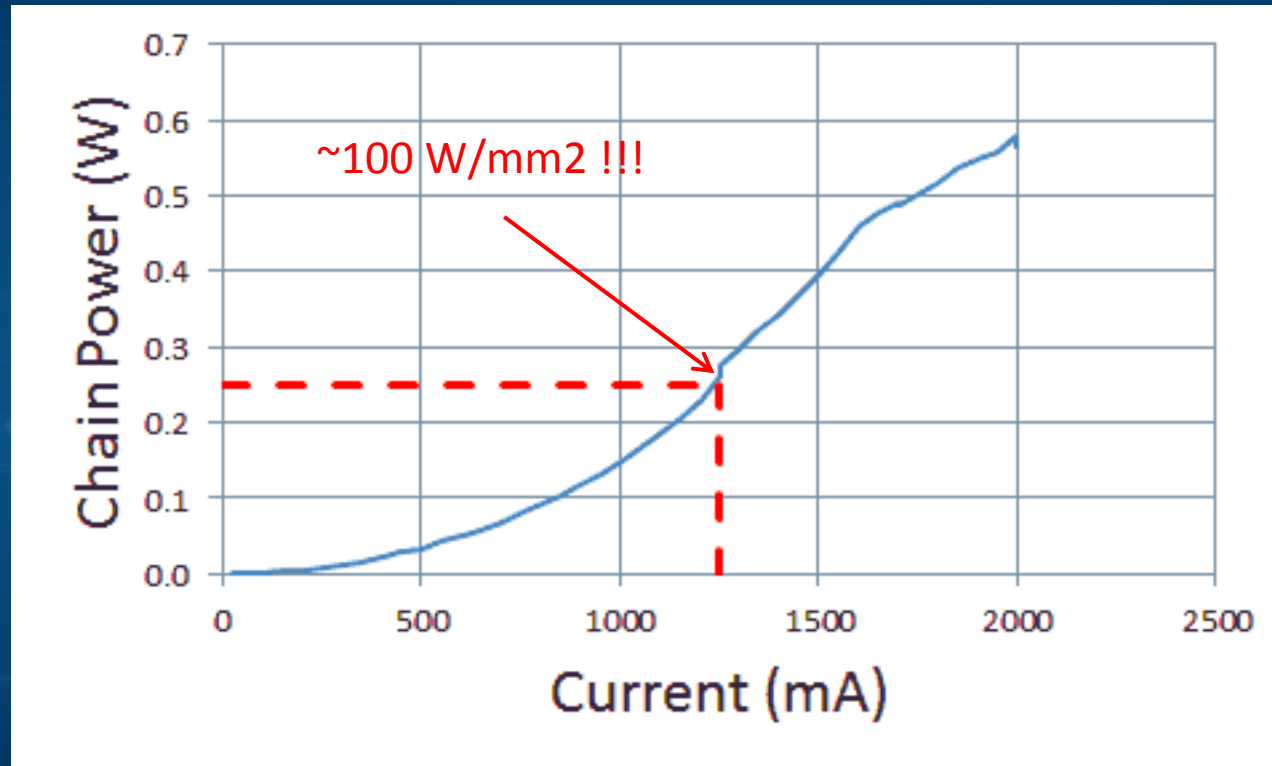
Touchdown contact yield of 99.9% demonstrated thus far.
-Limited by test parameters, not test vehicle.

DC Current Stress: 2-bump chain



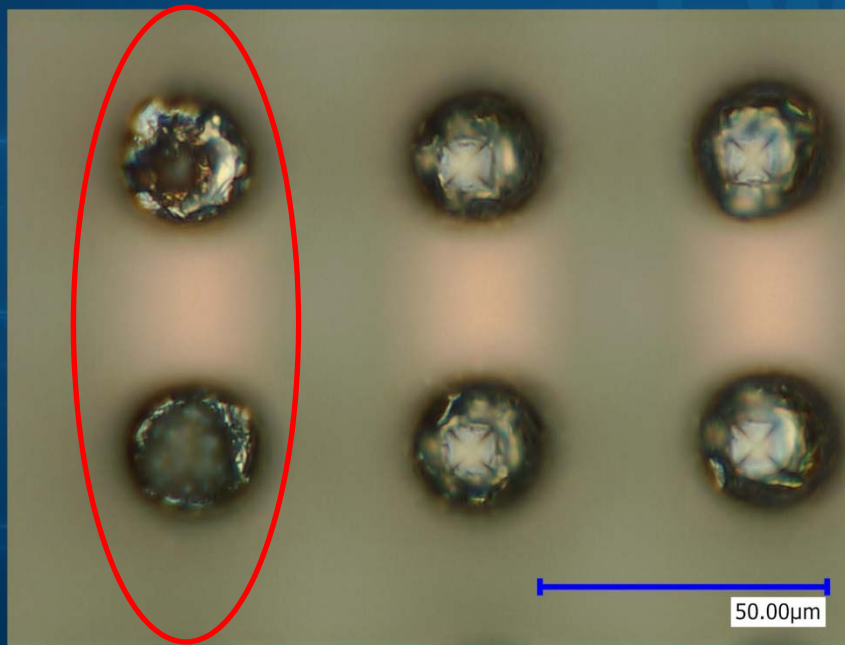
Joule heating apparent at ~ 500 mA.....
1A short-duration current should be acceptable.

Power Dissipation in 2-bump Chain

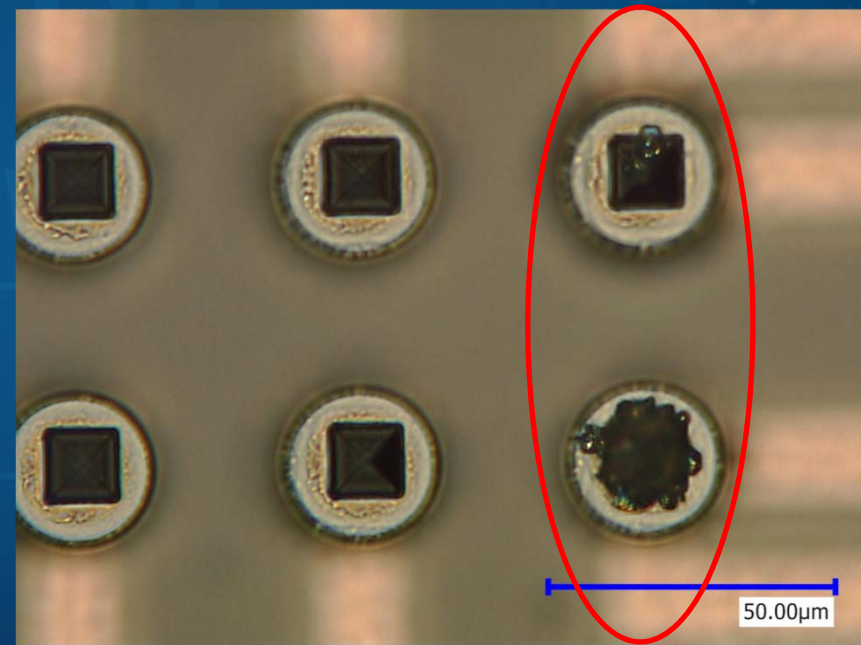


Post-Mortem

Current = 2A

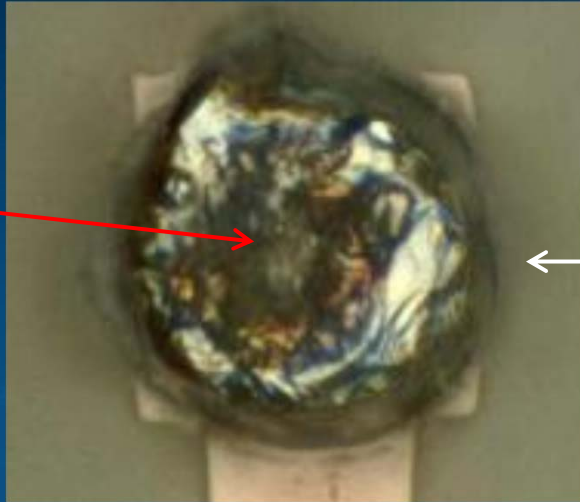


Current = 2A

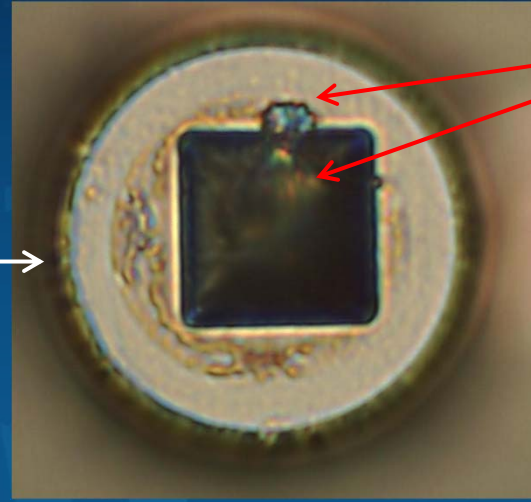


Post-Mortem (cont'd)

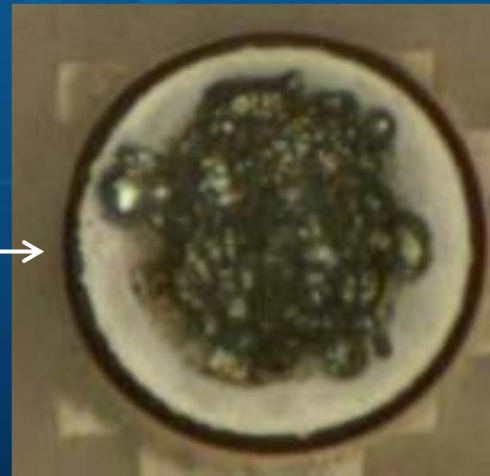
Tip indent
w/oxidation



Solder residue



Pull-out on
bump side



Touchdown Alignment

- **Stage movement accuracy $\sim \pm 1 \mu\text{m}$ (x,y,z)**
- **Homemade “semi-automatic” alignment procedure**
 - $X, Y, \theta \rightarrow \Delta x, \Delta y \sim \pm 1 \mu\text{m}$
- **Parallelism is biggest challenge**
 - No auto-leveling capability in prober (co-parallelism)
 - Have not yet found conditions for “gimbal-ing”
 - $\Delta z \sim \pm 2 \mu\text{m}$ over 12 mm die (0.01 deg tilt)
- **No probe damage or debris seen thus far**
 - < 100 touchdowns

Future Probe Stations

- **Area-array probing at pitches $< 50 \mu\text{m}$**
 - $> 100,000$ connections
- **Clean tool environment**
- **Flip-chip bonder capabilities**
 - Soften or melt solder
 - Controlled ambient
 - Vacuum , plasma, formic acid ...
- **Inexpensive, high-performance “smart” probe heads**

Transferrable Probe Tip (TPT) technology

- **Fine-pitch capability**
 - $< 50 \mu\text{m}$
- **Active-device probe head (“smart probe”)**
 - Low cost, high-speed test
- **Vertical probe without compliance**
 - Minimal damage and debris
 - High current capability
 - Disposable probe head

300 mm wafer capability.....

